Lianjia Wu

List of Publications by Year
in descending order

15	224	1040056 9	1125743 13
papers	citations	h-index	g-index

15	15	15	253
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Bottom-Up Nanofabrication with Extreme-Ultraviolet Light: Metalâ€“Organic Frameworks on Patterned Monolayers. ACS Applied Materials & Interfaces, 2021, 13, 43777-43786.	8.0	5
2	UV and VUV-induced fragmentation of tin-oxo cage ions. Physical Chemistry Chemical Physics, 2021, 23, 20909-20918.	2.8	8
3	Fluorescent Labeling to Investigate Nanopatterning Processes in Extreme Ultraviolet Lithography. ACS Applied Materials & Interfaces, 2021, 13, 51790-51798.	8.0	10
4	Extreme ultraviolet-excited time-resolved luminescence spectroscopy using an ultrafast table-top high-harmonic generation source. Review of Scientific Instruments, 2021, 92, 113004.	1.3	2
5	Unravelling the effect of fluorinated ligands in hybrid EUV photoresists by X-ray spectroscopy. Journal of Materials Chemistry C, 2020, 8, 14757-14765.	5.5	18
6	Universal direct patterning of colloidal quantum dots by (extreme) ultraviolet and electron beam lithography. Nanoscale, 2020, 12, 11306-11316.	5.6	27
7	Hybrid EUV Resists with Mixed Organic Shells: A Simple Preparation Method. European Journal of Inorganic Chemistry, 2019, 2019, 4136-4141.	2.0	16
8	Tuning photoionization mechanisms of molecular hybrid materials for EUV lithography applications. Journal of Materials Chemistry C, 2019, 7, 33-37.	5.5	18
9	Mechanistic insights in Zr- and Hf-based molecular hybrid EUV photoresists. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2019, 18, 1.	0.9	21
10	The role of the organic shell in hybrid molecular materials for EUV lithography. , 2019, , .		3
11	Photo-induced Fragmentation of a Tin-oxo Cage Compound. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 243-247.	0.3	15
12	Absorption coefficient of metal-containing photoresists in the extreme ultraviolet. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2018, 17, 1.	0.9	28
13	Ti, Zr, and Hf-based molecular hybrid materials as EUV photoresists. , 2018, , .		5
14	Absorption coefficient and exposure kinetics of photoresists at EUV. Proceedings of SPIE, 2017, , .	0.8	8
15	Complexation behavior of poly(acrylic acid) and lanthanide ions. Polymer, 2014, 55, 1183-1189.	3.8	40